

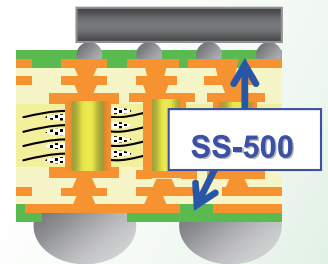


SS-500V2 (Trial # 65211)

LDA 用熱硬化型ソルダーレジストドライフィルム Thermal curable Dry Film Solder Resist for LDA Application

主な特徴 Feature

- **高 Tg / 低 CTE 材** : 他の PKG 用部材との熱挙動のマッチング
High Tg / Low CTE matched thermal behavior characteristic with other PKG materials
- **優れた電気特性 / PCT 耐性**
Excellent electrical property and PCT resistance
- **レーザー光源の選択による、短時間での小径 / 大径 SRO 加工対応**
Facilitating small / large diameter SRO in a short time by choice of laser light source
- **標準プロセスは、内層材プロセスおよびドライデスマプロセス対応**
Standard process facilitates interlayer material / dry desmear process



仕様 Specification

膜厚 Thickness	20 μm (Standard) – Adjustable
色調 Color	Green
保管条件 Storage condition	Below -15°C
標準硬化条件 Standard cure condition	170°C / 60min

特性 Properties

ガラス転移点 Tg *TMA method	165-175°C
線膨張係数 CTE α1	20-25ppm
弾性率 Young`s modulus	7.5-8.0GPa
破断点強度 Tensile strength	100-110MPa
伸び Elongation	2.0-3.0%
PCT 耐性 resistance (121°C/2atm/100%RH/200hrs)	No peeling
HAST 耐性 resistance (130°C/85%,12V,L/S=15/10 μm)	>400hrs (SR T=15 μm,n=6,MTTF60%)

レーザー光源による SRO 加工性比較 (SR Thickness=20 μm)

Comparison of SRO workability by laser light sources

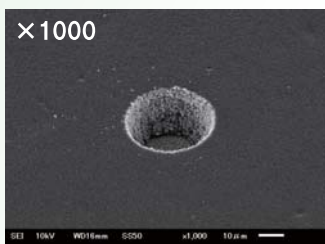


Fig. Top φ 30 μm by UV-YAG
Equipment :Hitachi via mechanics
Process time : 740holes/sec

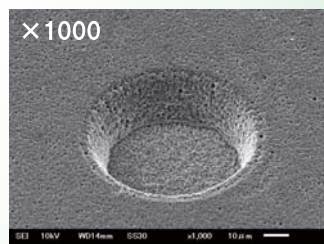


Fig. Top φ 65 μm by CO2 laser
Equipment :Hitachi via mechanics
Process time : 800holes/sec

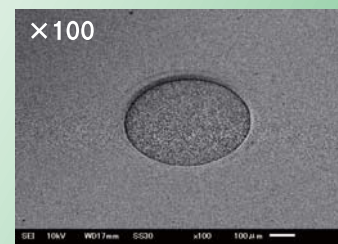


Fig. Top φ 500 μm by CO2 laser
Equipment : Mitsubishi Electric
Process time : 380holes/sec